

Express Mail No. **EV 346 810 878 US**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Cecile BERNE et al.

Confirmation No. 2144

Application No.: 10/733,431

Group Art Unit: 2812

Filing Date: December 10, 2003

Examiner:

For: TWO STAGE ANNEALING METHOD FOR
MANUFACTURING SEMICONDUCTOR
STRUCTURES

Atty. Docket No.: 4717-5499

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

Pursuant to applicants' duty of disclosure under 37 C.F.R. 1.56, applicants submit herewith (5) references for the Examiner's review and consideration. These references were cited in the European Search Report and a copy is enclosed.

These references are listed on the enclosed Form PTO-1449. It is respectfully requested that these references be made of record in this application by the Examiner's completion and return of the PTO Form 1449.

No fee is believed to be due for the filing of this statement as it is being submitted prior to an initial office action for this application. Should any fees be required, however, please charge such fees to Winston & Strawn LLP Deposit Account No. 50-1814.

Date: _____

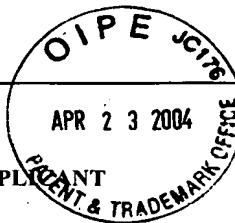
4/23/04

Respectfully submitted,

Allan A. Fanucci (Reg. No. 30,256)

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Enclosures



LIST OF REFERENCES CITED BY APPLICANT
(Use several sheets if necessary)

ATTY. DOCKET NO.:	APPLICATION SERIAL NO.:
4717-5499	10/733, 431
APPLICANT:	
Cecile BERNE et al.	
FILING DATE:	GROUP:
December 10, 2003	2812

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA	5,877,070	3/1999	Goesele et al.	438	458	
	AB	6,303,468	10/2001	Aspar et al.	438	455	
	AC						
	AD						
	AE						
	AF						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AG	FR 2767416 w/ English Abstract	2/1999	France			X	
	AH							
	AI							
	AJ							

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

	AK	B. Aspar et al: XP001050558 "The Generic Nature Of The Smart-Cut Process For Thin Film Transfer", Journal Of Electronic Materials, Vol. 30, No. 7, 22 , pp. 834-840, (2001)
	AL	B. Aspar et al: XP000884996, "Smart-Cut Technology: An Industrial Application Of Ion Implementation Induced Cavities", Materials Research Society Symposium Proceedings, Materials Research Society, Vol. 510, No. 13, pp 381-393 (19998)
	AM	

EXAMINER	DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.